Electron Beam Lithography Central Facility (@ Physics, IIT Bombay)

Booking request form for internal users (from IIT Bombay)

1	Name			
2	Department			
3	Date			
4	Are you a facility TA?			
5	Are you a fully trained (independent) user ?			
	Are you an assisted (by TAs only) user ?			
6	Slot preference:	TA assisted slot	9:00 – 12:00	12:00 – 15:00
		Independent user/ TA level user slot	15:00 – 18:00	18:00 – 21:00
7	Substrate material of your sample (e.g. Si/SiO2, GaAs, Sapphire etc..)			
8	Approximate size of the sample (max size 2cm x 2 cm) . Note: Maximum writing area = 1 mm x 1 mm			
9	Electron Beam Resist type required (e.g. PMMA 950/495 K A2/A4, HSQ…)			
10	Have you compiled the pattern with QCAD in your local PC/laptop ?			
11	Time required (1 slot = 3 hours, ask for two slots if the job is complex & has long write time)			
12	Confirm that the sample is free of any material that will outgass in vacuum (e.g. biological material, uncured resist etc)			

Note: The system is based on the following :
1. Zeiss Sigma 300 FE SEM https://www.zeiss.com/microscopy/en/products/sem-fib-sem/sem/sigma.html
2. NPGS v9 external pattern generator https://www.jcnabity.com/

Facility telephone 022 2159 6553